

Tres-Ark Liquid Dispense Module 2, 3 & 4 PLUS

PRODUCT DESCRIPTION

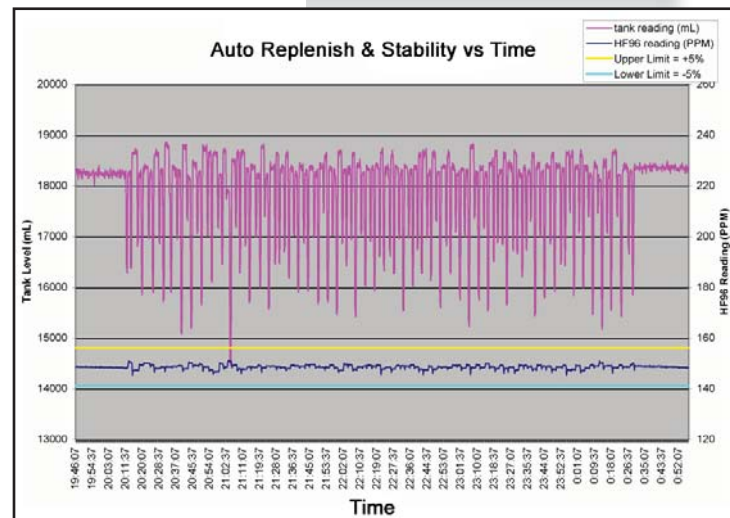
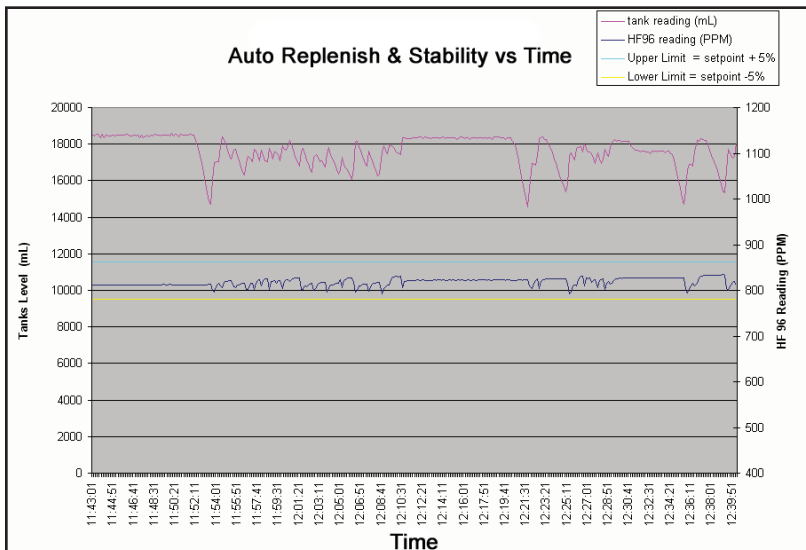
FractalFill™ Blending Products are turn-key solutions for implementing real-time closed loop control and dispense of multi-variant chemical mixes to meet exacting requirements in advanced semiconductor wafer cleaning and etching processes. The Tres-Ark Liquid Dispense Module 2, 3, & 4 PLUS, or TAK M2+, TAK M3+, and TAK M4+, supply multiple tools with two, three and four chemical mixes. Supplying up to eight chambers with the same homogeneous chemical mix drastically cuts down tool-to-tool variability.

FACILITY REQUIREMENTS (M2+, M3+, M4+)

Power -	208 - 240 vac single phase (2, 4, 6 amp)
CDA -	(48, 72, 96 SCFM) at 100 psig
N2 -	15 psi, 1/4" connection, 0.2 lpm
DIW -	55 - 60 psi, 3/4", (20, 40, 60 lpm)
Chemicals (2) -	30 - 60 psi: 1/4" connection, 1-3 lpm per module
Exhaust -	100 scfm: 4" connection
Drain -	3/4" connection, 15 gpm
Sump Drain -	1/2" connection
Flow Rate -	(24, 36, 48 lpm)
Pumps -	(4, 6, 8 pumps)

Contact for customization questions

FRACTALFILL™ BLENDING DATA



The chemical mix is always within the control limits even as demand levels fluctuate, as seen below



"bringing new technologies to the marketplace"

3709 Promontory Point
Dr., Suite 114
Austin, TX 78744 USA
www.tresark.com
512.804.0700
fax - 512.804.0900